

What is claimed is:

1. A method for fabricating a III-V Group compound semiconductor comprising a step of forming on a GaAs substrate by epitaxial growth an $\text{Al}_x\text{Ga}_{1-x}\text{As}$ multilayer structure ($0 \leq x < 1$) including a structure obtained by overlaying on a first layer of lower Al content a second layer of higher Al content, in which step the second layer is epitaxially grown on the first layer at a slower epitaxial growth rate than that used to epitaxially grow the first layer.

2. A method for fabricating a III-V Group compound semiconductor as claimed in claim 1, wherein the first layer is a buffer layer formed on the GaAs substrate.

3. A method for fabricating a III-V Group compound semiconductor as claimed in claim 1 or 2, wherein the first layer is a GaAs buffer layer formed on the GaAs substrate.

4. A method for fabricating a III-V Group compound semiconductor as claimed in claim 1, 2 or 3, further comprising a step of forming on the second layer by epitaxial growth at least one $\text{Al}_{y_j}\text{Ga}_{1-y_j}\text{As}$ layer ($0 \leq y_j < 1, j = 1, 2, \dots$).

5. A method for fabricating a III-V Group compound semiconductor comprising a step of successively epitaxially growing thin films to fabricate a III-V Group compound semiconductor composed of a buffer layer having a multilayer structure of thin-film layers of compositions represented by $\text{Al}_{x_i}\text{Ga}_{1-x_i}\text{As}$ ($0 \leq x_i < 1, i = 1, 2, \dots, n$) formed on a GaAs substrate and an upper multilayer structure of layers of compositions represented by $\text{Al}_{y_j}\text{Ga}_{1-y_j}\text{As}$ ($0 \leq y_j < 1, j = 1, 2, \dots$) formed on the buffer layer, wherein the Al content of an uppermost thin-film layer among the buffer layers is lower than the Al content of an adjacent upper multilayer structure layer formed on the uppermost thin-film layer, in which step a growth rate of the adjacent layer is made slower than a growth rate of the uppermost layer.

6. A method for fabricating a III-V Group compound semiconductor as claimed in claim 5, wherein the buffer layer is formed so that the Al contents of its thin-film layers increase stepwise from the GaAs substrate toward the upper multilayer structure.

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